

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant	:	Hirayama et al.
Appl. No.	:	10/590,046
Filed	:	June 15, 2007
For:	:	BASE MATERIAL FOR PATTERN-FORMING MATERIAL, POSITIVE RESIST COMPOSITION AND METHOD OF RESIST PATTERN FORMATION
Examiner	:	Johnson, C.
Group Art Unit	:	1795

**AMENDMENT AND RESPONSE TO OFFICE ACTION**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **March 17, 2010**, please consider the following remarks

**The listing of claims** begins on page 2 of this paper. No amendments have been made.

**Remarks** begin on page 9 of this paper.